

## Unlocking the Full Potential of Solar Cell Materials: Parameter Sensitivity Analysis and Optimization Using Response Surface Modelling

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**Table S1. Input parameters/variables for the device**

Parameter	SnSe	TiO <sub>2</sub> [1]	SnO <sub>2</sub>
Thickness (μm)	1.2	0.10	0.2
Band gap (eV)	1-1.5 [2]	2.26	3.6 [3]
Electron Affinity (eV)	4.2 [2], [4]	4.1-4.5	4.53 [3]
Valence band density of states (cm <sup>-3</sup> )	1.6 x10 <sup>18</sup>	6 x10 <sup>17</sup>	1 x10 <sup>19</sup> [5]
Conduction band density of states (cm <sup>-3</sup> )	1.45 x10 <sup>18</sup>	2 x10 <sup>17</sup>	1 x10 <sup>19</sup> [6]
Radiative recombination coefficient (cm <sup>3</sup> s <sup>-1</sup> )	2.9 x10 <sup>-11</sup>	1 x10 <sup>-8</sup>	1 x10 <sup>-8</sup>
Mobility of electron/hole (cm <sup>2</sup> /Vs)	130/56.7 [7]	100/50	5/2.5 [6]
Absorption coefficient	5 x10 <sup>4</sup> [2]	-	-
Uniform Acceptor density (cm <sup>-3</sup> )	9x10 <sup>15</sup> - 4x10 <sup>16</sup>	-	-
Uniform donor density (cm <sup>-3</sup> )	-	1x10 <sup>17</sup>	1x10 <sup>19</sup> [5]

Band gap of the TiO<sub>2</sub> is taken as 2.26 (which can be easily obtained after doping[8], [9]).

LAYER 1		SnSe		LAYER 2		TiO2	
thickness ( $\mu\text{m}$ )	1.200	uniform pure A (y=0)		thickness ( $\mu\text{m}$ )	0.100	uniform pure A (y=0)	
The layer is pure A: y = 0, uniform	0.000			The layer is pure A: y = 0, uniform	0.000		
Semiconductor Property P of the pure material	pure A (y = 0)			Semiconductor Property P of the pure material	pure A (y = 0)		
bandgap (eV)	1.380			bandgap (eV)	2.260		
electron affinity (eV)	4.200			electron affinity (eV)	4.200		
dielectric permittivity (relative)	12.500			dielectric permittivity (relative)	10.000		
CB effective density of states ( $1/\text{cm}^3$ )	1.450E+18			CB effective density of states ( $1/\text{cm}^3$ )	2.000E+17		
VB effective density of states ( $1/\text{cm}^3$ )	1.600E+18			VB effective density of states ( $1/\text{cm}^3$ )	6.000E+17		
electron thermal velocity (cm/s)	1.000E+7			electron thermal velocity (cm/s)	1.000E+7		
hole thermal velocity (cm/s)	1.000E+7			hole thermal velocity (cm/s)	1.000E+7		
electron mobility ( $\text{cm}^2/\text{Vs}$ )	1.300E+2			electron mobility ( $\text{cm}^2/\text{Vs}$ )	1.000E+2		
hole mobility ( $\text{cm}^2/\text{Vs}$ )	5.670E+1			hole mobility ( $\text{cm}^2/\text{Vs}$ )	5.000E+1		
<input type="checkbox"/> Allow Tunneling	effective mass of electron: 1.000E+0 effective mass of holes: 1.000E+0			<input type="checkbox"/> Allow Tunneling	effective mass of electron: 1.000E+0 effective mass of holes: 1.000E+0		
no ND grading (uniform)				no ND grading (uniform)			
shallow uniform donor density ND ( $1/\text{cm}^3$ )	0.000E+0			shallow uniform donor density ND ( $1/\text{cm}^3$ )	1.000E+17		
no NA grading (uniform)				no NA grading (uniform)			
shallow uniform acceptor density NA ( $1/\text{cm}^3$ )	4.000E+16			shallow uniform acceptor density NA ( $1/\text{cm}^3$ )	0.000E+0		

Figure S1 The input parameters for the SnSe (left ) and for TiO<sub>2</sub> (right) in SCAPS-1D.

Table S2. Set of parameters ( $z_i$ ) (with 5 variables, face-centered alpha =1.56508) using central composite design (CCD).

Sr. No.	$Z_1$	$Z_2$	$Z_3$	$Z_4$	$Z_5$
1	-1	-1	-1	-1	-1
2	1	-1	-1	-1	-1
3	-1	1	-1	-1	-1
4	1	1	-1	-1	-1
5	-1	-1	1	-1	-1
6	1	-1	1	-1	-1
7	-1	1	1	-1	-1
8	1	1	1	-1	-1
9	-1	-1	-1	1	-1
10	1	-1	-1	1	-1
11	-1	1	-1	1	-1
12	1	1	-1	1	-1
13	-1	-1	1	1	-1
14	1	-1	1	1	-1
15	-1	1	1	1	-1
16	1	1	1	1	-1
17	-1	-1	-1	-1	1
18	1	-1	-1	-1	1
19	-1	1	-1	-1	1
20	1	1	-1	-1	1
21	-1	-1	1	-1	1
22	1	-1	1	-1	1
23	-1	1	1	-1	1
24	1	1	1	-1	1

25	-1	-1	-1	1	1
26	1	-1	-1	1	1
27	-1	1	-1	1	1
28	1	1	-1	1	1
29	-1	-1	1	1	1
30	1	-1	1	1	1
31	-1	1	1	1	1
32	1	1	1	1	1
33	-1.56058	0	0	0	0
34	1.56058	0	0	0	0
35	0	-1.56058	0	0	0
36	0	1.56058	0	0	0
37	0	0	-1.56058	0	0
38	0	0	1.56058	0	0
39	0	0	0	-1.56058	0
40	0	0	0	1.56058	0
41	0	0	0	0	-1.56058
42	0	0	0	0	1.56058
43	0	0	0	0	0
44	0	0	0	0	0
45	0	0	0	0	0
46	0	0	0	0	0
47	0	0	0	0	0
48	0	0	0	0	0
49	0	0	0	0	0
50	0	0	0	0	0

**Table S3 Input parameters using the CCD for the simulation and their efficiency after simulation by SCAPS-1D**

Sr. No.	Band Gap (x <sub>1</sub> ) eV	Shallow Acceptor Density (x <sub>2</sub> ) 1/cm <sup>3</sup>	CBO(x <sub>3</sub> ) eV	W.F. (x <sub>4</sub> ) eV	Temp. (x <sub>5</sub> ) K	Efficiency (R) %
1	1	9 x10 <sup>+15</sup>	-0.1	4.8	275	15.77
2	1.5	9x10 <sup>+15</sup>	-0.1	4.8	275	9.02
3	1	4x10 <sup>+16</sup>	-0.1	4.8	275	17.12
4	1.5	4x10 <sup>+16</sup>	-0.1	4.8	275	9.84
5	1	9x10 <sup>+15</sup>	0.3	4.8	275	16.54
6	1.5	9x10 <sup>+15</sup>	0.3	4.8	275	9.17
7	1	4x10 <sup>+16</sup>	0.3	4.8	275	18.21
8	1.5	4x10 <sup>+16</sup>	0.3	4.8	275	10.23

9	1	$9 \times 10^{+15}$	-0.1	5.4	275	27.31
10	1.5	$9 \times 10^{+15}$	-0.1	5.4	275	19.97
11	1	$4 \times 10^{+16}$	-0.1	5.4	275	27.3
12	1.5	$4 \times 10^{+16}$	-0.1	5.4	275	19.98
13	1	$9 \times 10^{+15}$	0.3	5.4	275	29.95
14	1.5	$9 \times 10^{+15}$	0.3	5.4	275	19.47
15	1	$4 \times 10^{+16}$	0.3	5.4	275	29.95
16	1.5	$4 \times 10^{+16}$	0.3	5.4	275	20.01
17	1	$9 \times 10^{+15}$	-0.1	4.8	320	14.99
18	1.5	$9 \times 10^{+15}$	-0.1	4.8	320	9.23
19	1	$4 \times 10^{+16}$	-0.1	4.8	320	16.22
20	1.5	$4 \times 10^{+16}$	-0.1	4.8	320	10.18
21	1	$9 \times 10^{+15}$	0.3	4.8	320	14.68
22	1.5	$9 \times 10^{+15}$	0.3	4.8	320	8.85
23	1	$4 \times 10^{+16}$	0.3	4.8	320	16.1
24	1.5	$4 \times 10^{+16}$	0.3	4.8	320	9.98
25	1	$9 \times 10^{+15}$	-0.1	5.4	320	26.44
26	1.5	$9 \times 10^{+15}$	-0.1	5.4	320	18.8
27	1	$4 \times 10^{+16}$	-0.1	5.4	320	26.44
28	1.5	$4 \times 10^{+16}$	-0.1	5.4	320	18.85
29	1	$9 \times 10^{+15}$	0.3	5.4	320	27.18
30	1.5	$9 \times 10^{+15}$	0.3	5.4	320	17.94
31	1	$4 \times 10^{+16}$	0.3	5.4	320	27.18
32	1.5	$4 \times 10^{+16}$	0.3	5.4	320	18.42
33	0.85873	$2.45 \times 10^{+16}$	0.1	5.1	297.5	23.09
34	1.64127	$2.45 \times 10^{+16}$	0.1	5.1	297.5	13.26
35	1.25	$2.4126 \times 10^{+14}$	0.1	5.1	297.5	16.16
36	1.25	$4.87587 \times 10^{+16}$	0.1	5.1	297.5	20.21
37	1.25	$2.45 \times 10^{+16}$	-0.213	5.1	297.5	16.7
38	1.25	$2.45 \times 10^{+16}$	0.413	5.1	297.5	17.82
39	1.25	$2.45 \times 10^{+16}$	0.1	4.63048	297.5	9.31
40	1.25	$2.45 \times 10^{+16}$	0.1	5.56952	297.5	29.94
41	1.25	$2.45 \times 10^{+16}$	0.1	5.1	262.286	21.69
42	1.25	$2.45 \times 10^{+16}$	0.1	5.1	332.714	18.1
43	1.25	$2.45 \times 10^{+16}$	0.1	5.1	297.5	19.98
44	1.25	$2.45 \times 10^{+16}$	0.1	5.1	297.5	19.98
45	1.25	$2.45 \times 10^{+16}$	0.1	5.1	297.5	19.98
46	1.25	$2.45 \times 10^{+16}$	0.1	5.1	297.5	19.98
47	1.25	$2.45 \times 10^{+16}$	0.1	5.1	297.5	19.98
48	1.25	$2.45 \times 10^{+16}$	0.1	5.1	297.5	19.98
49	1.25	$2.45 \times 10^{+16}$	0.1	5.1	297.5	19.98
50	1.25	$2.45 \times 10^{+16}$	0.1	5.1	297.5	19.98

**Tablx10 S4. Actual value of the efficiency from SCAPS-1D software and the predicted value of the efficiency by RSM model and their Residual.**

<b>Run Order</b>	<b>Actual Value of Efficiency</b>	<b>Predicted Value of Efficiency</b>	<b>Residual</b>
1	18.10	18.84	-0.7404
2	9.98	9.36	0.6159
3	19.98	19.86	0.1225
4	18.21	18.26	-0.0487
5	9.84	10.38	-0.5394
6	27.30	28.02	-0.7165
7	10.18	10.05	0.1303
8	16.10	15.99	0.1110
9	18.80	19.09	-0.2909
10	19.98	19.86	0.1225
11	9.23	8.59	0.6389
12	10.23	10.70	-0.4688
13	23.09	24.51	-1.42
14	9.02	8.92	0.0992
15	15.77	15.23	0.5392
16	16.22	15.42	0.7954
17	29.94	28.40	1.54
18	16.54	16.80	-0.2602
19	19.98	19.81	0.1709
20	9.17	9.24	-0.0702
21	13.26	12.91	0.3522
22	19.98	19.86	0.1225
23	16.70	17.45	-0.7504

24	19.98	19.86	0.1225
25	16.16	18.00	-1.84
26	20.01	20.13	-0.1185
27	27.31	27.63	-0.3180
28	20.21	19.44	0.7661
29	14.99	13.97	1.02
30	17.12	16.69	0.4307
31	21.69	20.87	0.8155
32	26.44	26.75	-0.3118
33	19.47	19.74	-0.2700
34	18.85	19.48	-0.6294
35	8.85	7.91	0.9444
36	19.98	19.86	0.1225
37	29.95	29.59	0.3641
38	14.68	14.53	0.1495
39	19.98	19.86	0.1225
40	19.97	19.42	0.5495
41	17.94	18.41	-0.4653
42	27.18	27.32	-0.1362
43	27.18	26.93	0.2523
44	9.31	11.32	-2.01
45	17.82	18.14	-0.3220
46	19.98	19.86	0.1225
47	26.44	26.36	0.0767
48	19.98	19.86	0.1225
49	29.95	29.20	0.7526
50	18.42	18.79	-0.3738

The figure shows two side-by-side screenshots of the SCAPS 3.3.10 Layer Properties Panel. The left panel is for SnSe and the right panel is for TiO2. Both panels show material properties, doping profiles, and absorption models.

Property	SnSe (Layer 1)	TiO2 (Layer 2)
Thickness (μm)	1.200	0.100
The layer is pure A: y = 0, uniform	0.000	0.000
Semiconductor Property P of the pure mater	pure A (y = 0)	pure A (y = 0)
bandgap (eV)	1.000	2.260
electron affinity (eV)	4.200	4.364
dielectric permittivity (relative)	12.500	10.000
CB effective density of states (1/cm <sup>3</sup> )	1.450E+18	2.000E+17
VB effective density of states (1/cm <sup>3</sup> )	1.600E+18	6.000E+17
electron thermal velocity (cm/s)	1.000E+7	1.000E+7
hole thermal velocity (cm/s)	1.000E+7	1.000E+7
electron mobility (cm <sup>2</sup> /Vs)	1.300E+2	1.000E+2
hole mobility (cm <sup>2</sup> /Vs)	5.670E+1	5.000E+1
effective mass of electrons	1.000E+0	1.000E+0
effective mass of holes	1.000E+0	1.000E+0
no ND grading (uniform)	no ND grading (uniform)	no ND grading (uniform)
shallow uniform donor density ND (1/cm <sup>3</sup> )	0.000E+0	1.000E+17
no NA grading (uniform)	no NA grading (uniform)	no NA grading (uniform)
shallow uniform acceptor density NA (1/cm <sup>3</sup> )	2.890E+16	0.000E+0
Absorption interpolation model	alpha pure A material (y=0)	alpha pure A material (y=0)
List of absorption submodels present:	sqrt(hv-Eg) law (SCAPS traditional)	sqrt(hv-Eg) law (SCAPS traditional)

Figure S2. Input panel for the (left) SnSe, and (right) TiO<sub>2</sub>.

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